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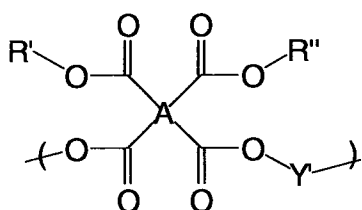
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(54) Title: ANTIREFLECTIVE COMPOSITION FOR PHOTORESISTS



(1)

(57) **Abstract:** The invention relates to an antireflective coating composition for a photoresist layer comprising a polymer, a crosslinking agent and an acid generator, where the polymer comprises at least one unit of structure (1), where, A is a nonaromatic linking moiety, R' and R'' are independently selected from hydrogen, Z and W-OH, where Z is a (C₁-C₂₀) hydrocarbyl moiety and W is a (C₁-C₂₀) hydrocarbyl linking moiety, and, Y' is independently a (C₁-C₂₀) hydrocarbyl linking moiety. The invention further relates to a process for imaging the antireflective coating composition.

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